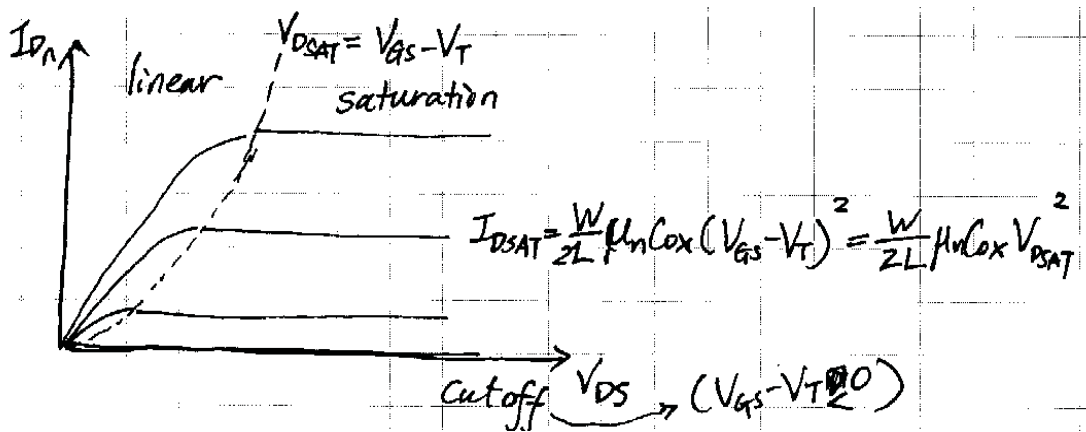


Recitation 10: MOSFET VI Characteristics - Channel Length Modulation & Back Gate Effect

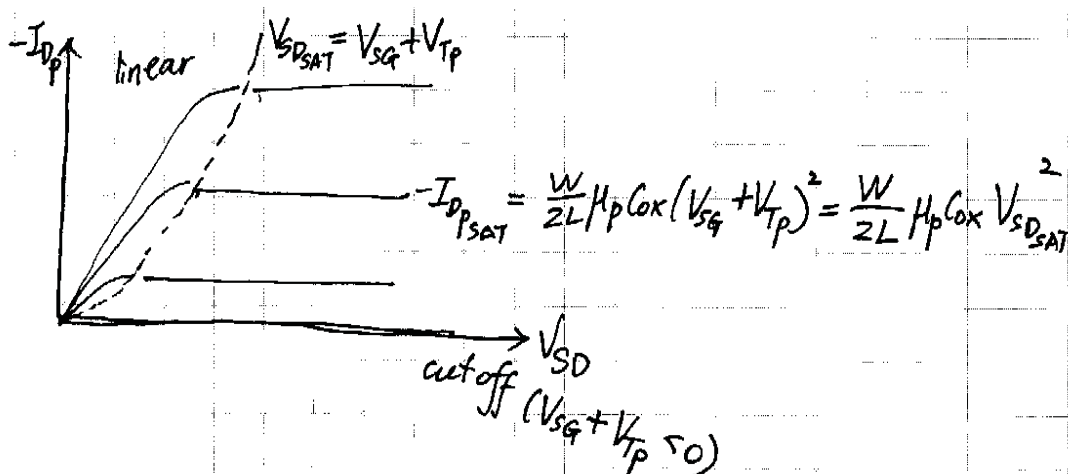
Yesterday we discussed two more aspects in MOSFET IV characteristics.

- Channel length modulation
- Backgate effect

Here is the n-MOS IV characteristic (ideal, no channel length modulation)



What about the IV characteristic for a p-MOS?

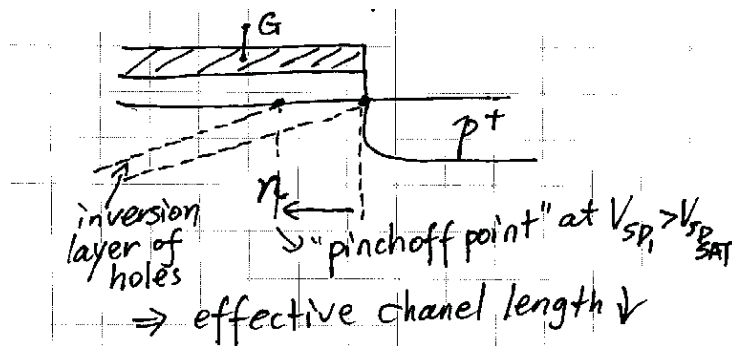


Channel Length Modulation

NMOS

What happens when $V_{DS} = V_{GS} - V_T$?

$$|Q_n(L)| = C_{ox}(V_{GS} - V_{DS} - V_T) = 0$$

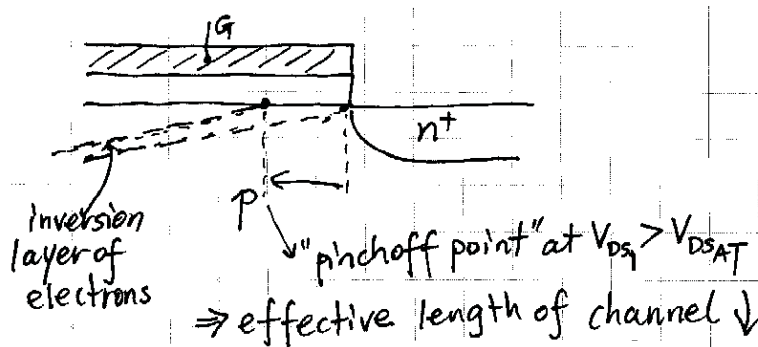


$$I_{DS} = \frac{w}{2L} \mu_n C_{ox} (V_{GS} - V_T)^2 \quad L \downarrow I_{DS} \uparrow$$

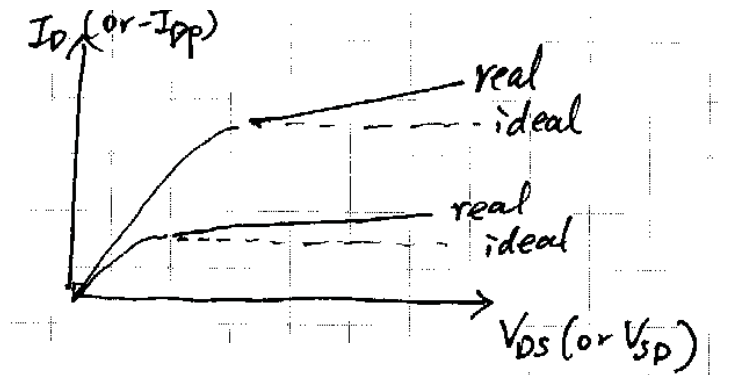
PMOS

When $V_{SD} = V_{SG} + V_{Tp}$,

$$|Q_p(L)| = C_{ox}(V_{SG} - V_{SD} + V_{Tp}) = 0$$



As a result,



To model it, we have:

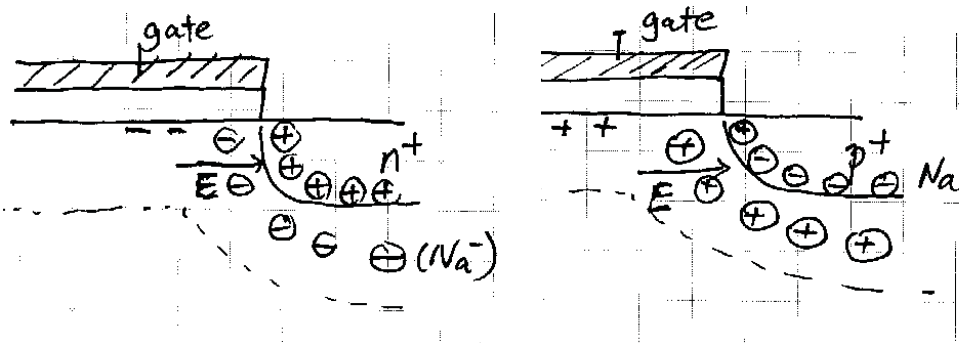
$$I_D \approx \frac{w}{2L} \mu_n C_{ox} (V_{GS} - V_T)^2 (1 + \lambda V_{DS})$$

$$(\text{or } -I_{Dp} \approx \frac{w}{2L} \mu_p C_{ox} (V_{SG} + V_{Tp})^2 (1 + \lambda V_{SD}))$$

$$\text{e.g. } \lambda = \frac{0.1 \mu\text{m}}{L} \text{V}^{-1}$$

The ideal case is the ideal current source, now we have a current source with some internal resistance (will talk about this later).

Note: pinch-off region does not impede current flow near drain (high lateral E-field near drain makes them go fast)



Backgate Effect

NMOS

When $V_{BS} = 0$,

$$\begin{aligned} V_T &= V_{FB} - 2\phi_p + \frac{1}{C_{ox}} \sqrt{2\epsilon_s q N_a (-2\phi_p)} \\ (V_{FB} &= -(\phi_{gate} - \phi_{body})) \end{aligned}$$

When $V_{BS} < 0$,

$$V_T(V_{BS}) = V_{FB} - 2\phi_p + \frac{1}{C_{ox}} \sqrt{2\epsilon_s q N_a (-2\phi_p - V_{BS})}$$

Backgate effect parameter:

$$\begin{aligned} \gamma &= \frac{1}{C_{ox}} \sqrt{2\epsilon_s q N_a} \\ V_T(V_{BS}) &= V_{TO} + \gamma(\sqrt{-2\phi_p - V_{BS}} - \sqrt{-2\phi_p}) \end{aligned}$$

PMOS

When $V_{BS} = 0$,

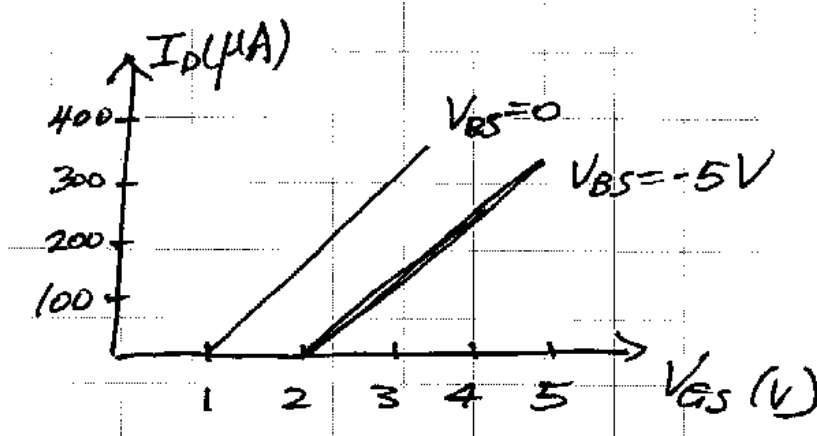
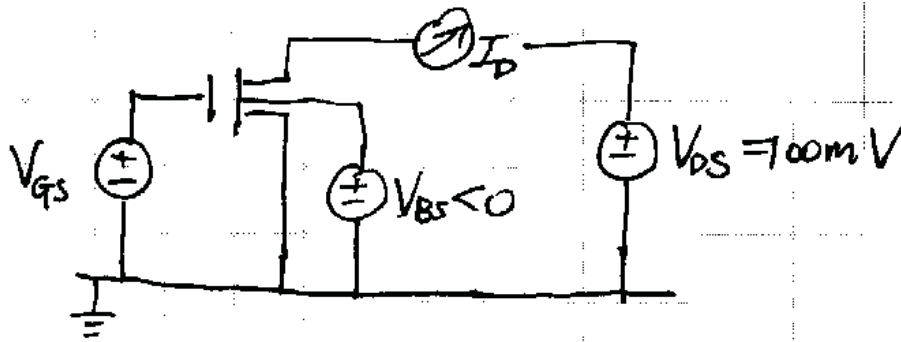
$$\begin{aligned} V_{Tp} &= V_{FB} - 2\phi_n - \frac{1}{C_{ox}} \sqrt{2\epsilon_s q N_d (+2\phi_n)} \\ (V_{FB} &= -(\phi_{gate} - \phi_{body})) \end{aligned}$$

When $V_{SB} < 0$, or $V_{BS} > 0$

$$\begin{aligned} V_{Tp}(V_{SB}) &= V_{FB} - 2\phi_n - \frac{1}{C_{ox}} \sqrt{2\epsilon_s q N_d (2\phi_n - V_{SB})} \\ \gamma &= \frac{1}{C_{ox}} \sqrt{2\epsilon_s q N_d} \\ V_{Tp}(V_{SB}) &= V_{Tpo} - \gamma(\sqrt{2\phi_n - V_{SB}} - 2\sqrt{\phi_n}) \end{aligned}$$

Exercise

NMOS, channel doping $N_a = 10^{17} \text{ cm}^{-3}$



V_{GS} vary from $0 \rightarrow 5 \text{ V}$, $V_{BS} = 0, -5 \text{ V}$. $V_{Tn} = 10 \text{ V}$ when $V_{BS} = 0$; $V_{Tn} = 2 \text{ V}$ when $V_{BS} = -5 \text{ V}$. What is γ_n ? What is C_{ox} ?

$$\gamma_n = \frac{1}{C_{ox}} \sqrt{2\epsilon_s q N_a} \text{ to find } \gamma_n, \text{ need to know } C_{ox}$$

$$V_{Tn}(V_{BS}) = V_{Tn0} + \gamma_n (\sqrt{-2\phi_p - V_{BS}} - \sqrt{-2\phi_p}) \quad \phi_p = -0.42 \text{ V}$$

$$2 \text{ V} = 1 \text{ V} + \gamma_n (\sqrt{0.84 \text{ V} + 0.5 \text{ V}} - \sqrt{0.84 \text{ V}}) \implies \gamma_n = 0.67 \text{ V}^{\frac{1}{2}}$$

$$C_{ox} = \frac{1}{\gamma_n} \sqrt{2\epsilon_s q N_a} = \frac{1}{0.67 \text{ V}^{\frac{1}{2}}} \sqrt{2 \times 1 \times 10^{-12} \text{ F/cm} \times 1.6 \times 10^{-19} \text{ C} \times 10^{17} \text{ cm}^{-3}}$$

$$= 2.7 \times 10^{-7} \text{ F/cm}^2$$

When $V_{GS} = 3 \text{ V}$, $V_{DS} = 0.1 \text{ V}$, $V_{BS} = 0 \text{ V}$, what is the channel electron charge density at

the drain?

$$|Q_n(L)| = C_{\text{ox}}(V_{\text{GS}} - V_{T_{n_0}} - V_{\text{DS}}) = 2.7 \times 10^{-7} \text{ F/cm}^2 \times (3 - 1 - 0.1) \text{ V} =$$

When $V_{\text{DS}} = 0.1 \text{ V}$, $V_{\text{GS}} = 3 \text{ V}$, $V_{\text{BS}} = -5 \text{ V}$, what is the channel electron charge density at the drain?

$$|Q_n(L)| = C_{\text{ox}}(V_{\text{GS}} - V_{T_n}(V_{\text{BS}}) - V_{\text{DS}}) =$$

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6.012 Microelectronic Devices and Circuits
Spring 2009

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